



THIN FILM MEASUREMENTS AT NUFAB

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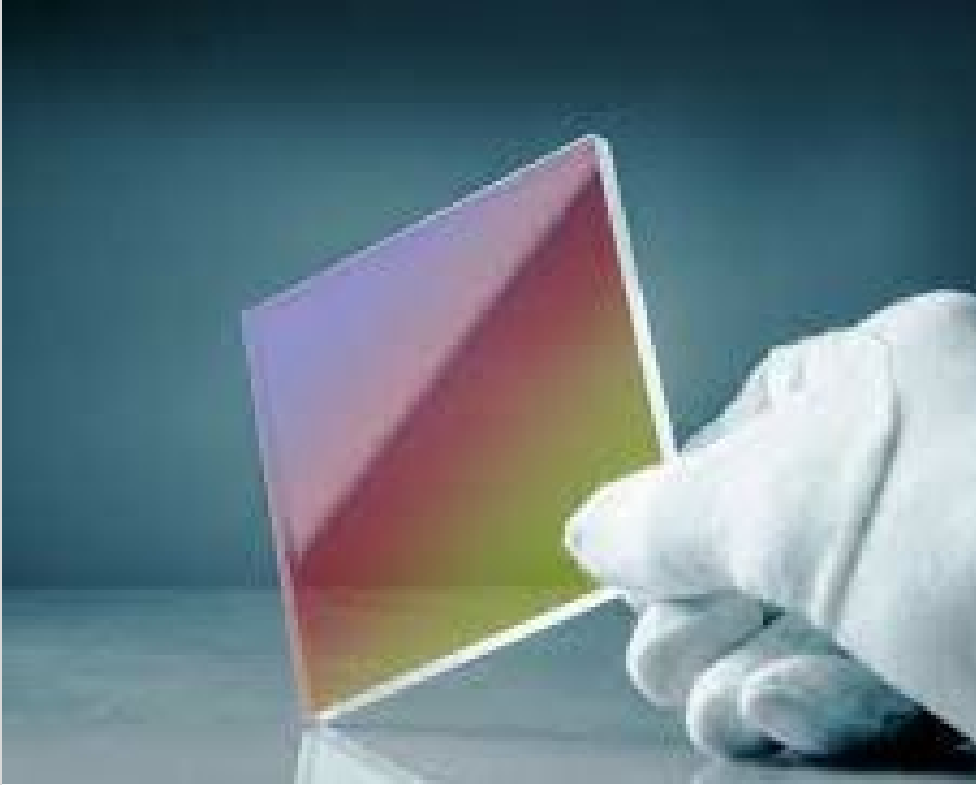
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Outline

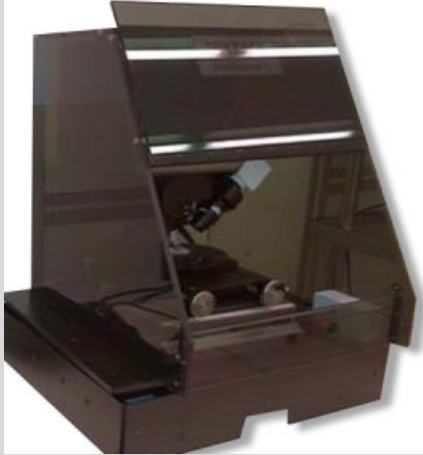
- Available equipment at NUFAB
- Working principles and limits
- Parameter comparison
- How to choose an equipment

Thin film characterization



- Thickness
- Optical constants, n & k
- Roughness
- Mechanical properties, e.g. stress
- Electrical properties, e.g. sheet resistance

Available equipment at NUFAB



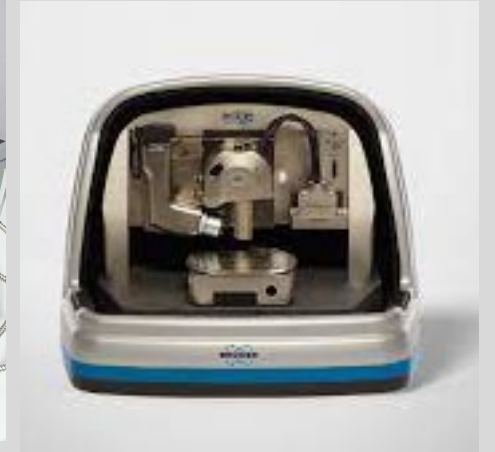
Profilometer
Dektak



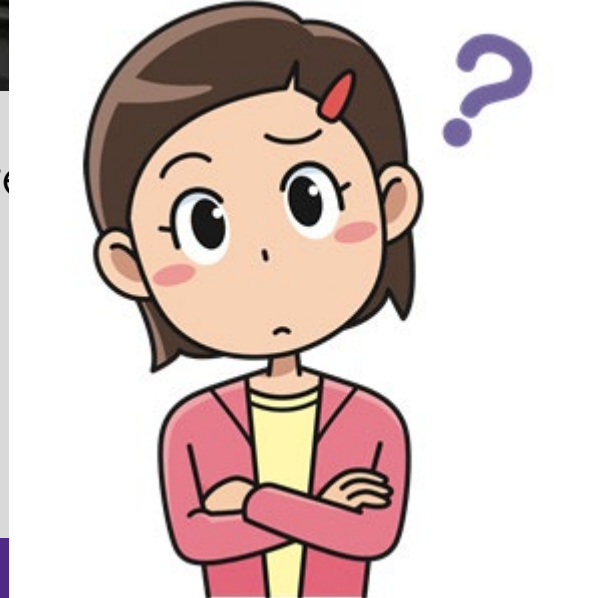
Optical Profilometer
Zygo



reflectometer
Filmetrics

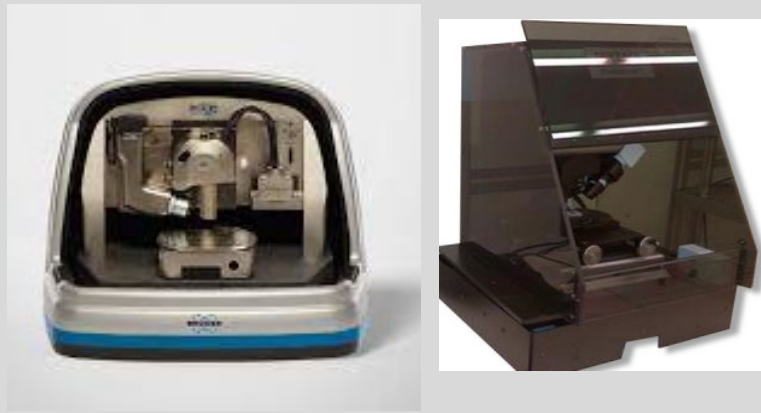
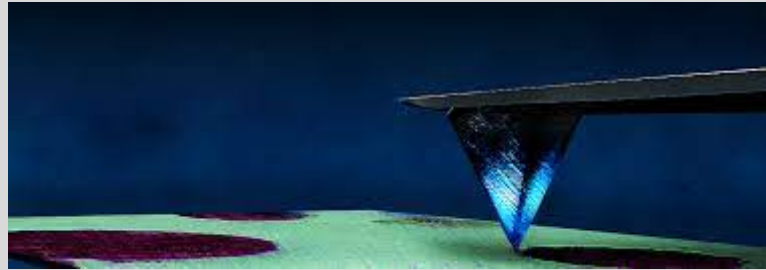


AFM
Bruker



Two major categories

Mechanical – usually contact



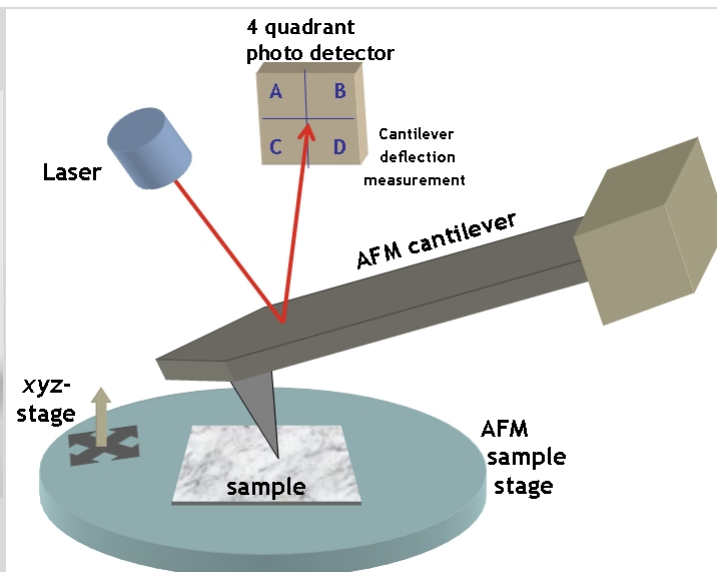
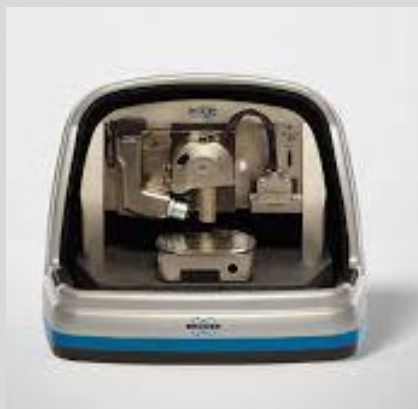
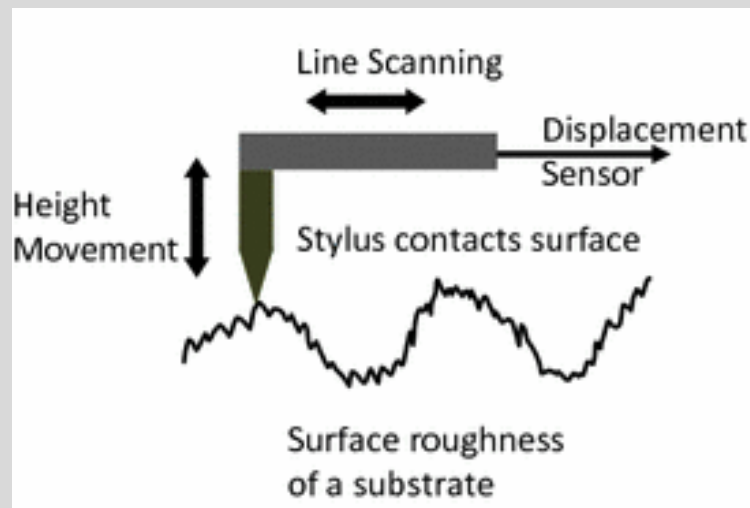
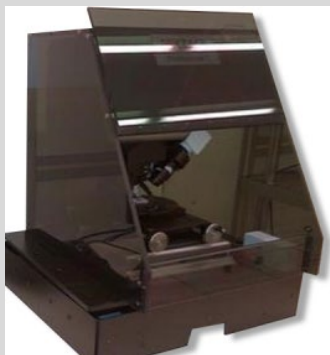
AFM, profilometer

Optical - noncontact



Optical profilometer, ellipsometer, reflectometer

Mechanical methods



Measures

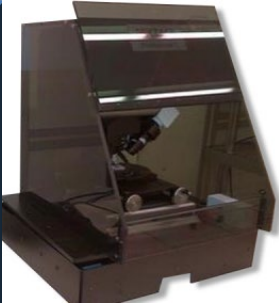

1. Thickness, roughness
2. Mechanical properties
3. Not optical properties

Pros:

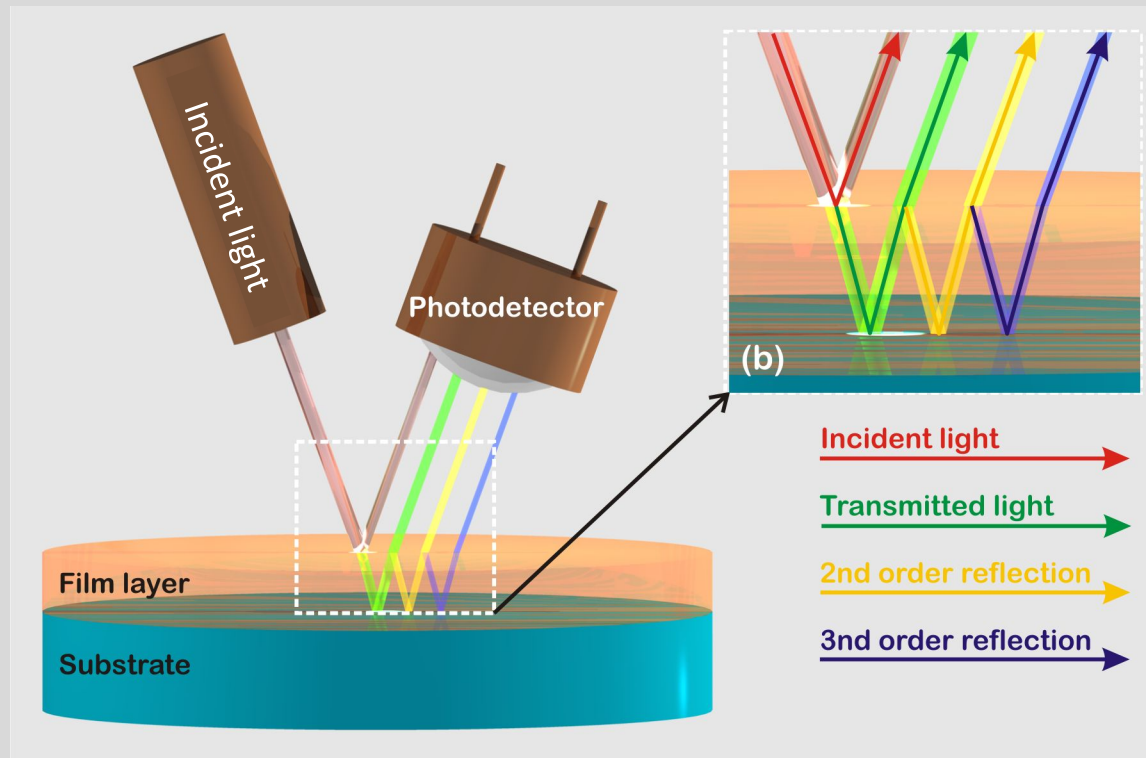
1. **Signal reliable**
2. Regardless film optical properties

Cons:

1. Signal to noise ratio - measurement setting tuning
2. Requires a step to measure film thickness
3. Contact measurement (except AFM noncontact mode).
4. Relatively slow measurement, especially for mapping

	 Profilometer Dektak	 AFM Bruker Edge
Measured properties	Thickness, roughness, stress	Thickness, roughness
Thickness range	50 nm – 1mm	1 nm – 10 μm
Height resolution	4~10 nm	sub nm
Lateral measurement range/resolution	Range: < 8 inch Resolution: 5 μm	Range: < 90 μm
Speed	Defined by user, typical: 0.5mm, 20 sec	

Optical methods



Measures

1. Thickness, roughness
2. Optical constants (except zygo)
3. Not mechanical properties

Pros:

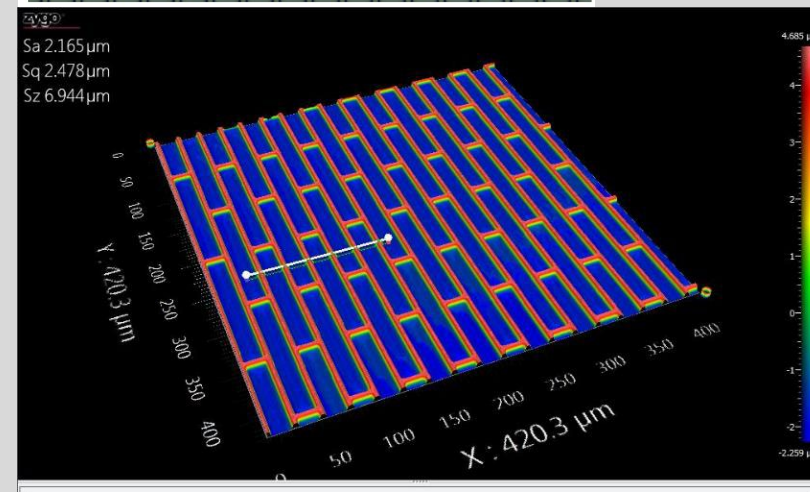
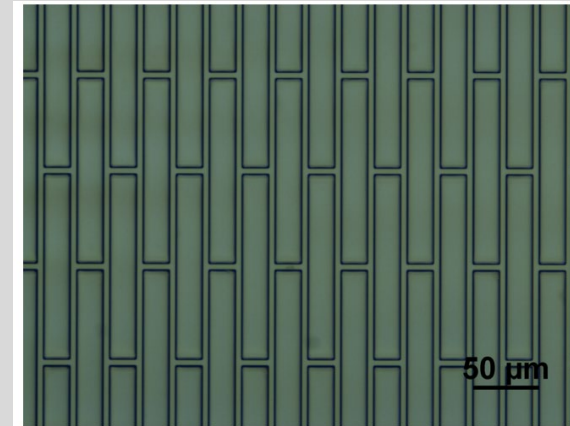
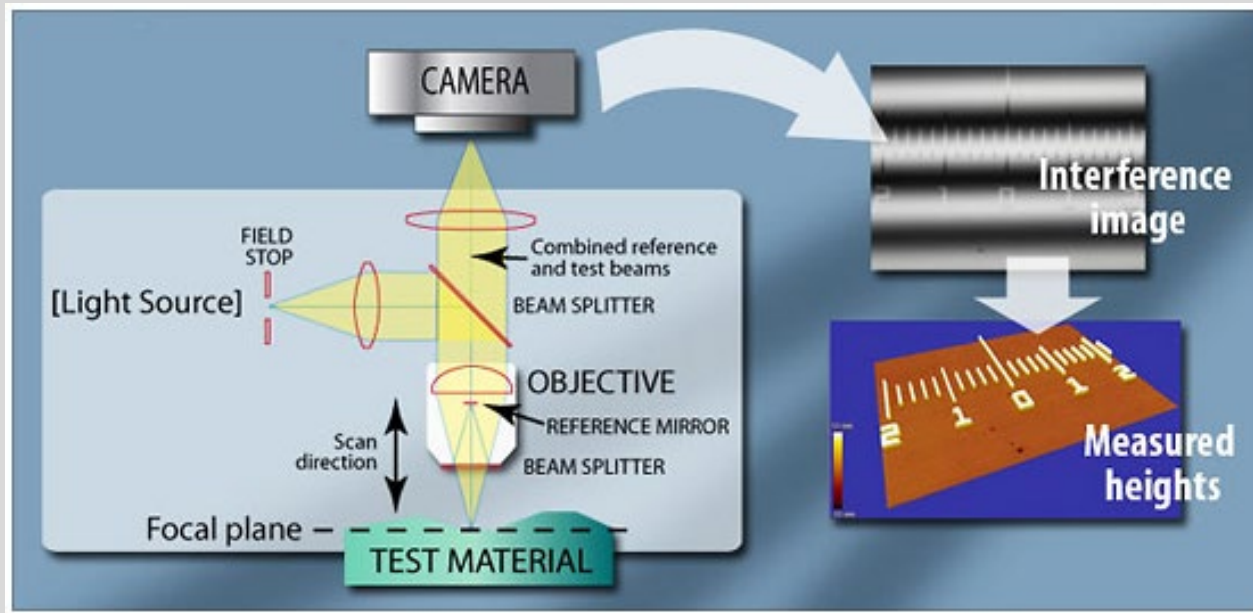
1. Noncontact
2. High resolution
3. Fast
4. Don't need a step to measure thickness (except zygo)

Cons:

1. Complex signal analysis, usually involves modeling and fitting
2. Usually have material limits

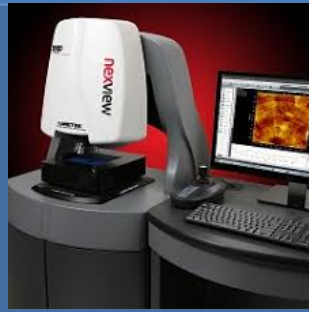
Optical method 1: interference

Optical profilometer - Zygo



Compares incident and reflected light
Measures surface topography with high resolution, fast and 3D mapping

Ref: <https://www.zygo.com/support/technologies/csi-techology>



Optical
profilometer
zygo



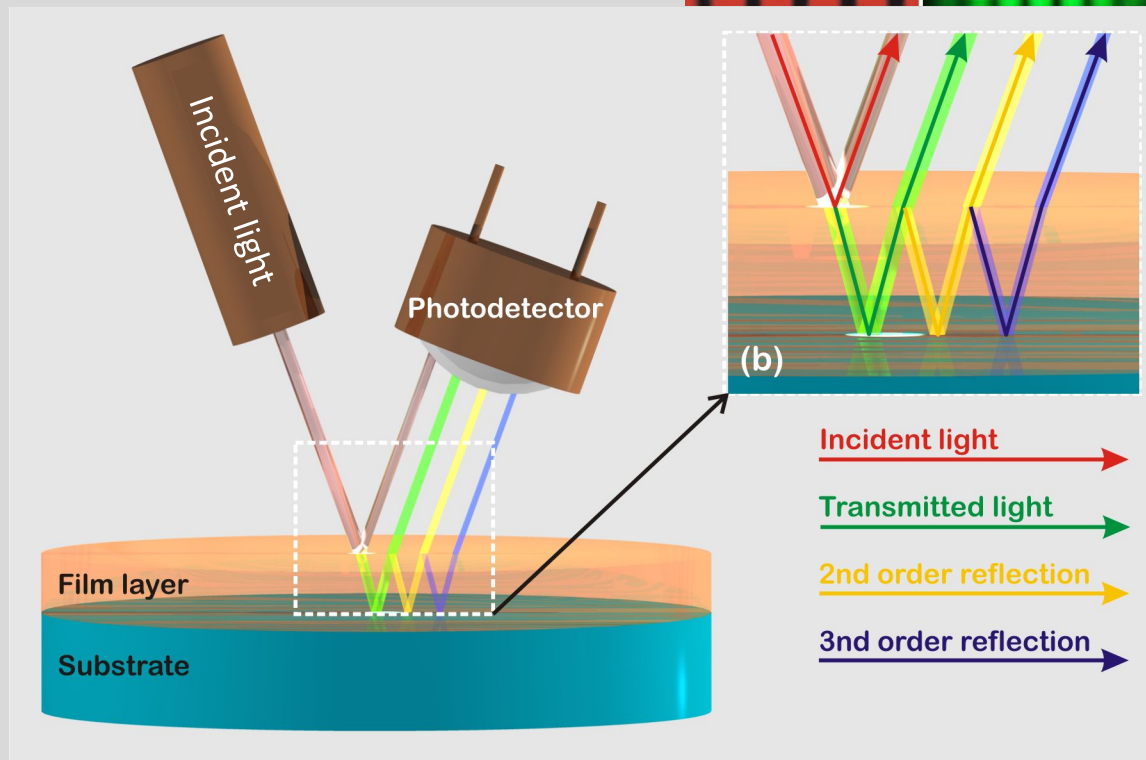
Profilometer
Dektak



AFM
Bruker

Working principle	Optical – interference	Mechanical	Mechanical
Measured properties	Thickness, roughness	Thickness, roughness, stress	Thickness, roughness
Thickness range	Sub nm - 1mm	50 nm – 1mm	1 nm -10 μm
Height resolution	Sub nm	4~10 nm	Sub nm
Lateral measurement range/resolution	Range: 3.3 x 3.3 mm ² without stitch, 8 inch with stitch Res. : 1 μm	Range: 8 inch Res. : 5 μm	Range: 90 μm
Speed	Height dependent, Usually < 1min	Defined by user, typical: 20 sec for 0.5mm line scan	

Zygo limit

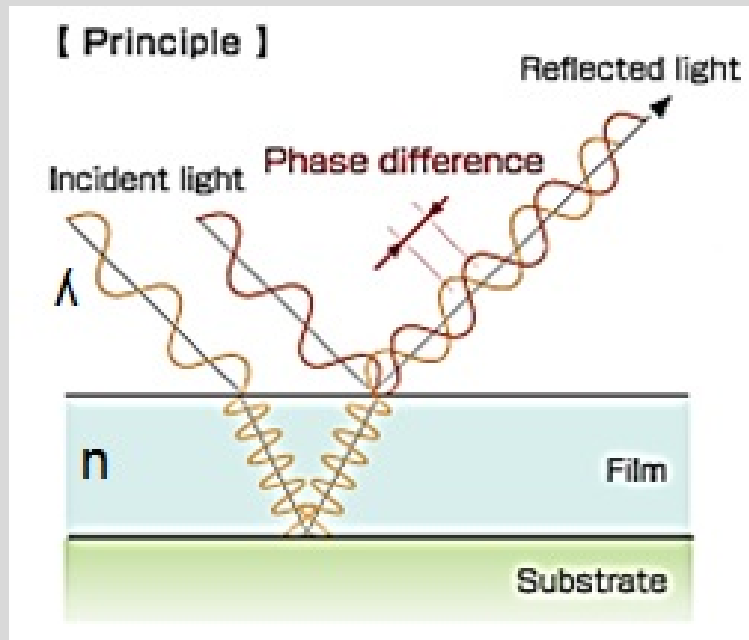


1. Eliminate the transmitted light
---- opaque films
2. If transparent, separate the interferences
---- thick films, usually $> 10 \mu\text{m}$

Another interference measurement



Reflectometer - Filmetrics



Specially for transparent films

Pros:

1. Quick and easy measurement
2. Easy modeling

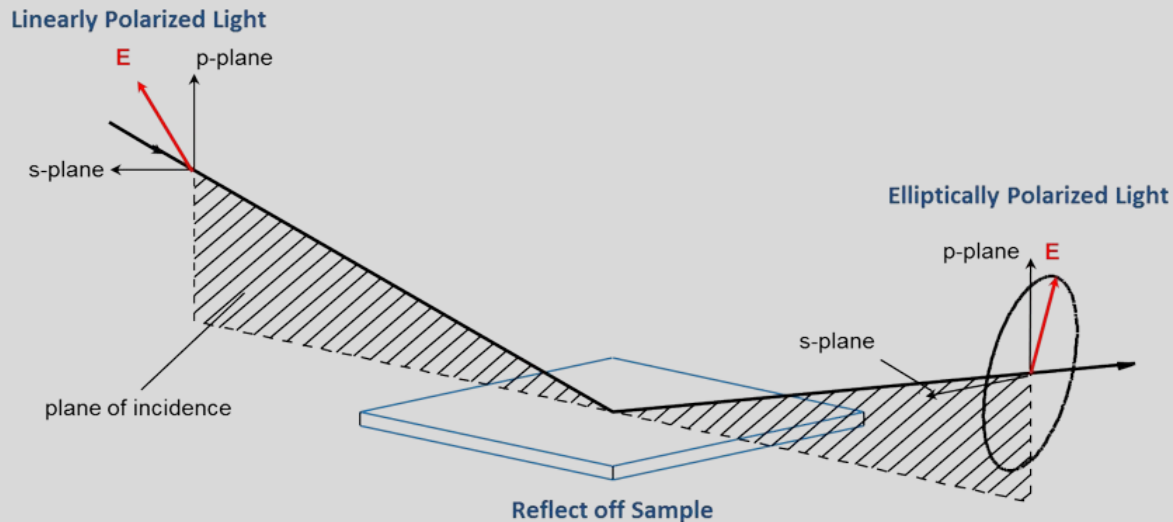
Cons:

1. Transparent or semi-transparent film
2. Known material, i.e. well characterized n & k

Ref: <https://www.filmetrics.com/technology>

Optical method 2: ellipsometry

Ellipsometer – J. A. Woollam



Measure the change in polarization after the light interact with the material



Pros:



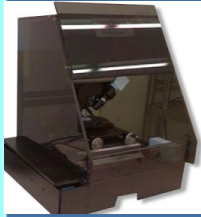

1. Quick and easy measurement
2. High sensitivity, can measure films of 1 nm
3. Works well with unknown materials

Cons:

1. Modeling may not be easy
2. Limited to transparent or semi-transparent films

Ref: <https://register.gotowebinar.com/recording/4749616861388349199>

	 Reflectometer	 Ellipsometer
Measured properties	Thickness, roughness, n&k	Thickness, roughness, n&k
Thickness range	15 nm – 50 μm	1 nm – 10 μm
Lateral measurement range/resolution	Signal averaged over 3mm Dia.	Signal averaged over 3mm Dia.
Material limit	Known, transparent or semi-transparent	Transparent or semi-transparent
Speed	< 1min	< 1min

	Reflectometer / ellipsometer	Optical profilometer	Profilometer	AFM
				
Working principle	Optical – interference /ellipsometry	Optical – interference	Mechanical	Mechanical
Measured properties	Thickness, roughness Optical constants	Thickness, roughness	Thickness, roughness, stress	Thickness, roughness
Thickness range	15nm – 50 μm/ 1nm – 10 μm	Sub nm - 1mm	50 nm – 1mm	1 nm – 10 μm
Height resolution	1 nm, modeling matters	Sub nm	4~10 nm	Sub nm
Lateral range /resolution	Average over 3mm dia.	Range: 8 inch with stitch Res. : 1 μm	Range: 8 inch Res. : 5 μm	Range: 90 μm
Speed	~ 1min	Height dependent, Usually < 1min	Defined by user, typical: 20 sec for 0.5mm line scan	

Example cases

Q1: Measure photoresist thickness

A1: profilometer – Dektak (preferred) or reflectometer

Q2: Measure etching depth

A2: If photoresist is still there, use profilometer-Dektak. If not, profilometer-Dektak or optical one –zygo

Q3: Measure a PECVD or LPCVD film. Don't want to create a step

A3: Reflectometer or ellipsometer

Q4: Measure films by e-beam evaporator or thermal evaporator, or metal films by sputter

A4: During deposition, cover the substrate partially to create a step. Measure with profilometer –Dektak (preferred) or optical profilometer – zygo

Q5: Measure films by ALD

A5: Ellipsometer

Q6: Need a beautiful 3D picture for publication

A6: optical profilometer –zygo or AFM depending the scan area. Try to fit your sample in.



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